

# Total Energy Electronic Structure Calculations: From Silicon to Carbon 60\*

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We report microscopic total-energy electronic-structure calculations for the materials ranging from typical semiconductors to exotic new materials. The calculations have been performed within the local density approximation (LDA) in density functional theory. The results and their comparison with experiments elucidate success and limitation of LDA.

## I. Introduction

To explain and then predict phenomena in nature on the basis of ab initio calculations are fascinating challenges in science. Local density approximation (LDA) in density functional theory<sup>[1]</sup> has been shown to be an effective tool for such challenges<sup>[2]</sup>. Although the LDA fails to describe excited states in condensed matters quantitatively<sup>[3]</sup>, it provides very accurate structural and electronic informations about their ground states. In this talk, I will present total-energy electronic-structure calculations within the LDA for several materials. I start with an issue of the Si vacancy which is a paradigm of defects in semiconductors, and also contains important aspects in semiconductor physics. I next report the results for microscopic mechanisms for arsenic substitutional adsorption on the Si(100) surface which is generally regarded as an initial stage of epitaxial growth. Finally, I discuss electronic structures of doped fullerenes. An emphasis is put on alkaline-earth doped fullerenes which have recently been discovered to be superconducting.

## II. Calculation

Since details have been given elsewhere<sup>[4,5]</sup>, I will give only a brief description of the calculational method.

First, nuclei and core electrons are simulated by pseudopotentials which are generated by atomic (ionic) LDA calculations. They are normconserving<sup>[6]</sup> and have high transferability. Second, interactions among valence electrons are treated by the LDA in density functional theory. For the exchange-correlation energy, we use the Ceperley-Alder form<sup>[7]</sup> as is parametrized by Perdew and Zunger<sup>[8]</sup>. Third, plane waves are used as basis to expand valence-electron wavefunctions and thus valence-electron charge density<sup>[9]</sup>. In large-scale calculations, electron-degrees-of-freedom is conveniently optimized to minimize the total energy, or in other words an effective Schrodinger (Kohn-Sham) equation is solved, by iterative methods. The preconditioned conjugate-gradient-method which we use is an example. We also use the conjugate-gradient-method to optimize nuclear(ionic)-degrees-of-freedom (geometry optimization). We adopt an alternative minimization procedure in which the electron-degrees-of-freedom and the ionic-degrees-of-freedom are optimized consecutively<sup>[10]</sup>, in contrast with the simultaneous optimization<sup>[11]</sup>. The calculational conditions, such as the validity of the Kleinman-Bylander approximation<sup>[12]</sup>, the sizes of supercells used in calculations, the cutoff energies in the plane-wave-basis sets, the number of k points in Brillouin zone for the integration, etc, are well examined to obtain reliable results<sup>[4]</sup>.

This LDA describes several aspects in condensed

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\*Invited talk.

i.e., covalency, flexibility of bond network, i.e., elasticity, and effect of charge transfer among different atoms, i.e., ionicity, are satisfactorily described in the LDA. Electron correlation is not completely treated in the LDA, but it is partially included in the scheme. Phenomena in condensed matters are regarded as a competition among these interactions. Hence it is not surprising that the LDA nicely describes phenomena in real materials.

### III. Vacancy in silicon

An example which exhibits such a competition is the vacancy in Si crystal. If we remove a Si atom from the crystal, we have a vacancy which induces deep levels in the gap between valence and conduction bands. The deep levels consist mainly of four  $sp^3$  dangling bonds generated by removing the Si atom. Actually, a state named  $a_1$  with totally symmetric linear combination of the dangling bond orbitals appears just below the valence-band-top. The remaining three states with the symmetry of  $t_2$  appear in the center of the gap. In the case of the neutral vacancy, two electrons are accommodated in this triply degenerate level. We thus expect Jahn-Teller type, symmetry-lowering distortion around the vacancy. This is a competition between hybridization, or the rebonding energy, and the elasticity. Further, we have more than one electron in the deep level so that electron correlation is also expected to play a role.

In fact, for negatively-charged vacancy  $V^-$ , there has been a controversy about the effect of electron correlation. From the Electron Paramagnetic Resonance (EPR) measurement<sup>[13]</sup>, the Jahn-Teller distortion is considered to take place, and the symmetry lowers from  $T_d$  to  $C_{2v}$ . But semiempirical molecular orbital theory combined with the estimate of Jahn-Teller energy does not lead to the ground state of this symmetry<sup>[14]</sup>. Hence, it has been argued that the electron correlation is important and its explicit inclusion, as in the configuration interaction treatment, is necessary to explain

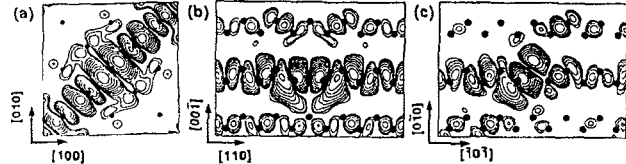


Figure 1: Contour plots of the wavefunction of the deep level in  $V^{-1}$ : (a) in the (001) plane, (b) in the (110) plane, and (c) in the (101) plane. The Si lattice sites are shown by solid circles, and the vacancy is situated at the center of each figure.

the experiment.

However, the LDA calculation provides nice results<sup>[5]</sup>. The total-energy optimization for the 216-site supercell leads to a stable rebonded geometry in which both Jahn-Teller-type symmetry-lowering distortion and the breathing-type symmetry-keeping distortion take place. The obtained geometry has the symmetry of  $C_{2v}$ , which is consistent with the EPR experiment. In the geometry each two of four dangling bonds forms a pair, and there is an energy barrier from this geometry to another equivalent geometry in which different two dangling bonds form a pair. The calculated barrier is 0.12 eV which is comparable with the corresponding experimental value of 0.07 eV.

Figure 1 is a wavefunction of the deep level of  $V^-$ . In general, wavefunctions of deep levels are considered to be localized. But a surprise in Figure 1 is, although it is indeed localized, the wavefunction is extended in an anisotropic fashion. There are atomic chains along  $\{110\}$  direction in diamond structure. The wavefunction of the deep level of  $V^-$  extends along this direction. We also observe some distortions in the back-bond region around the vacancy. We can compare this wavefunction with Electron-Nuclear-Double-Resonance (ENDOR) measurement<sup>[15]</sup>. To quantify the comparison, we show both theoretical and experimental values of the wavefunction at each Si site around the vacancy in Figure 2. It is clear that the experimental values of the wavefunction along  $\{110\}$  direction is much larger than the values at another Si sites, in accord with the present calculation. The agreement between the calculation and the experiment is satisfactorily good.

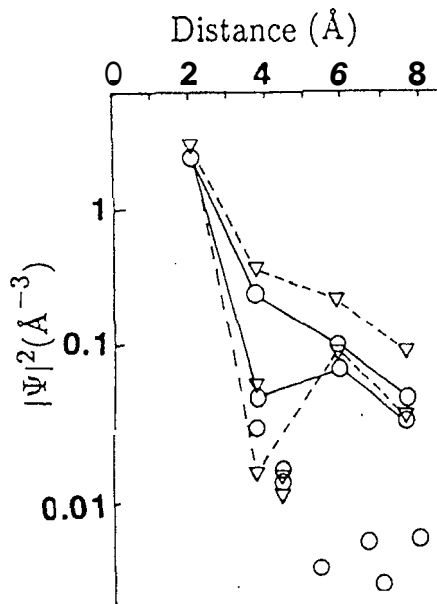


Figure 2: The amplitude of the wavefunction at nuclear sites plotted against the distance from the vacancy site. Calculated results are shown by circles and the ENDOR data are shown by triangles. The atomic sites on the zigzag chains in the {110} plane are connected by solid lines (calculated results) and dashed lines (ENDOR data).

#### IV. Substitutional arsenic adsorption on silicon (100)

The next example is the substitutional As adsorption on the Si(100) surface. This is regarded as an initial stage of heteroepitaxial growth of GaAs on Si which is of technological importance. The Si(100) surface exhibits a well-known dimerized structure: Each two of top-layer Si atoms forms a dimer and the dimers are lined up in one direction, leading to  $2 \times 1$  structure. Atomic steps are always observed. The commonly observed are single-layer and bilayer steps. When the surface is slightly misoriented, e.g., inclined toward {110} direction by several degrees, it shows the bilayer steps dominantly; the bilayer step named DB in which the dimers on each terrace are parallel to the step edges.

In case that As is adsorbed on this Si(100) by one monolayer, what we would naturally expect is the  $1 \times 2$  structure with As dimers: The As atoms are adsorbed on the  $2 \times 1$  Si surface, break the existing Si dimers, and form new As dimers. The resulting As dimers are

rotated by  $90^\circ$  compared with the original Si dimers just because of an inherent feature of the diamond structure. This is what is actually observed in experiments at low temperature ( $T < 400^\circ\text{C}$ )<sup>[16,17]</sup>. At higher temperature ( $400^\circ\text{C} < T < 600^\circ\text{C}$ ), however, it is observed<sup>[16,17]</sup> that the surface shows the  $2 \times 1$  dimerized structure with the top-layer As dimers unrotated compared with the original Si dimers.

To explain this surprising phenomenon Alerhand et al. have performed total energy calculations for the two types of bilayer steps for the As-covered Si(100)<sup>[18]</sup>. They have found that one type where the As dimers are parallel to the step edges has lower energy than the other where the dimers are perpendicular to the edges. This implies that the dimer-rotated  $1 \times 2$  structure made by the As adsorption is metastable. A counter-argument that substitutional As adsorption occurs on a terrace has come from Tromp et al. based on low-energy electron microscopy and scanning tunneling microscopy (STM) measurements<sup>[19]</sup>. They consider that the As atoms on top replace the underlying Si atoms, leading to a  $2 \times 1$  reconstruction of the As-covered surface. In both arguments, the relaxation of the surface stress is the only driving force for the phenomenon: It is considered to be relaxed at the step edges in the former, and on the terrace in the latter. Further, little is known about reaction pathways toward the lower energy states.

We here propose a microscopic mechanism to explain this phenomenon occasionally called the sublattice dilemma. We present the total-energy electronic-structure calculations which support a dimer exchange mechanism in which As dimers adsorbed on top of the dimerized Si surface substitute the sub-surface Si atoms, and then the Si atoms displaced diffuse to another site on the terrace or, more likely, to step edges. The driving force for the exchange is not surface-stress as was imagined but newly discovered  $\pi$  bonding between the top-layer and the subsurface-layer Si atoms<sup>[20]</sup>.

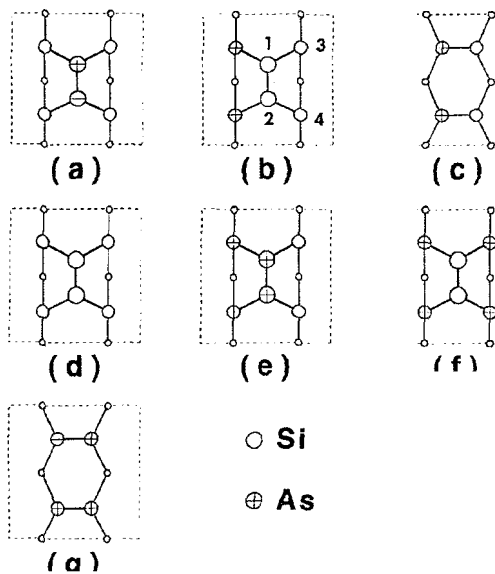


Figure 3: Schematic top views of several geometries in the exchange mechanism for substitutional As adsorption on Si(100). The open and the crossed circles represent Si and As atoms, respectively. (a) As dimer on Si(100), (b) Si dimer on underlying As (the numbered Si atoms are referred in text), (c) As-Si heterodimer on Si(100), (d) Si dimer on Si(100), (e) As dimer on underlying As and Si atoms, (f) Si dimer on underlying four As atoms, and (g) As dimers on Si(100). Each figure depicts a half of the  $2 \times 2$  periodic cell in the lateral directions which is used in the present calculations.

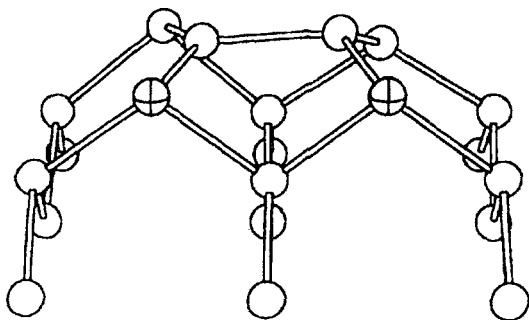


Figure 4: Stable geometry after substitutional As adsorption on Si(100), corresponding to the schematic illustration of Fig. 3 (b). The open and the crossed spheres denote the Si and As atoms, respectively.

The first geometry in the dimer exchange process is shown in Fig. 3(a): Arsenic atoms break a Si dimer and an As dimer is formed on the Si  $2 \times 1$  dimerized surface. The As dimer is rotated by  $90^\circ$  with respect to the Si dimers. We have examined a dimer exchange process in which the two As atoms in Fig. 3(a) substitute the sub-surface Si atoms. The resulting geometry is a Si dimer on the 2 As and 2 Si atoms (Fig. 3(b)). The calculated heat of formation of this reaction is calculated to be 0.7 eV: The dimer exchange is an exothermic reaction.

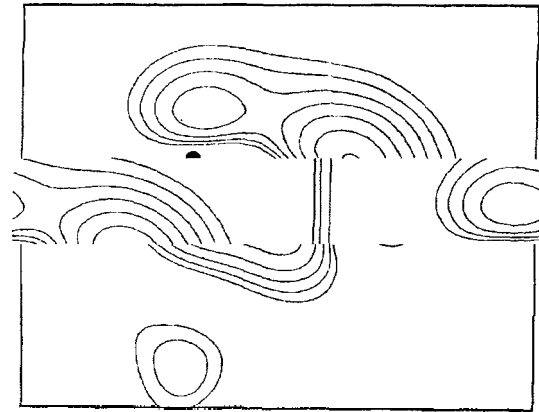


Figure 5: Charge density of an occupied state near the surface Brillouin zone boundary ( $k = \pi/2a_0(3/8, 3/8, 0)$ ). A  $\pi$  bond between Si(2) and Si(4) denoted by the solid circles is shown on the vertical plane cutting the two Si atoms. The value of the highest contour is  $3.5 \times 10^{-3} \text{ e}/(\text{a.u.})^3$ , and the subsequent contours differ by a factor of 1.65.

The geometry after dimer exchange is accurately determined by the LDA calculation as in Fig. 4. We observe a flexible reconstruction of the top layer Si atoms. They are buckled and flattened considerably. As a result, the distance between the top-layer Si and the sub-surface Si becomes shorter than the distance between the two top-layer Si atoms. The wavefunction below the Fermi level in this geometry plotted in a plane which contains the top-layer Si and the sub-surface Si is shown in Fig. 5. The wavefunction exhibits  $\pi$ -bonded character between the top-layer and the sub-surface Si atoms. In other words, electronic structure changes from metallic to semiconducting upon the dimer exchange. This is the origin of the energy gain in the exchange process.

Next, these Si atoms are desorbed from the site (Fig.3(b)) and diffuse to another site on a terrace (Fig.3(d)), or a step edge. The remaining atoms form two As-Si hetero-dimers as in Fig.3(c). The total-energy difference between the initial and the final states in this reaction is calculated to be 0.4 eV. Again this reaction of the desorption and the subsequent diffusion is exothermic. The next dimer exchange could take place on the As-Si hetero-dimer site. New As atoms come to break the hetero-dimer and form a As dimer (Fig.3(e)). These As atoms again substitute the sub-surface Si atoms (Fig.3(f)), and then the displaced Si

atoms could diffuse away (Fig.3(d)). The calculated heat of formation is 0.8 eV for this exchange reaction, and it is 0.6 eV for the subsequent diffusion reaction. Both are exothermic reactions.

The As dimers formed by these consecutive exothermic reactions (Fig.3(g)) are unrotated compared with the starting Si dimerized surface. The sublattice dilemma is naturally explained. Of course there are several competing processes, such as As diffusion process before the exchange. But what I like to emphasize is that the dimer exchange process is exothermic, and the reason for the exothermicity is the new  $\pi$ -bonded structure between the top-layer and the sub-surface layer Si atoms, or in other words, the flexible reconstruction in the resulting geometry.

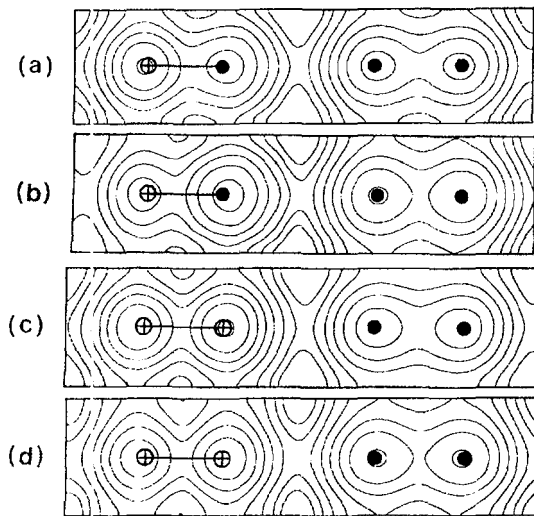


Figure 6: Calculated tunneling current density for the As-Si heterodimer with bias voltage (a)  $V = -2$  eV, (b)  $V = -1$  eV, and the As dimer with (c)  $V = -2$  eV, and (d)  $V = -1$  eV. In the right half of each figure, the current density for the averaged Si asymmetric dimer is shown. The crossed circles denote the position of As atoms. The values of the highest contour are  $3.10 \times 10^{-4} \text{ e}/(\text{a.u.})^3$  in (a),  $1.85 \times 10^{-4} \text{ e}/(\text{a.u.})^3$  in (b),  $3.88 \times 10^{-4} \text{ e}/(\text{a.u.})^3$  in (c), and  $1.70 \times 10^{-4} \text{ e}/(\text{a.u.})^3$  in (d), respectively. The subsequent contours differ by a factor of 1.5.

Fig. 6 is the calculated images in scanning tunneling microscopy (STM) of the As-Si hetero-dimer and the As dimer, along with the image of the Si dimer. We note several interesting features. In the As-Si hetero-dimer, the As site becomes brighter with increasing the bias voltage (with including lower states below the

Fermi level). This is the consequence that the energy of the As dangling bond, which constitutes the As-Si hetero-dimer, is lower than that of the Si dangling bond. We observe a change in brightness with varying the bias voltage also for the As dimer. In any case, we find significant difference among the Si dimer, the As dimer and the As-Si hetero-dimer. Hence experimental observation of these images could be an evidence for the dimer exchange mechanism presented here.

## V. Alkaline-earth doping in solid $C_{60}$

We now move to a story of  $C_{60}$  which has a unique shape of a soccer ball with 60 carbon atoms located at the 60 vertices of the ball<sup>[21]</sup>. The carbon soccer balls were found to be condensed in a crystalline form<sup>[22]</sup>, and it is a semiconductor with an energy gap of about 2 eV<sup>[23,24]</sup>. Alkali-atom doping makes this material metallic and superconducting with the transition temperature  $T_c$  more than 30 K<sup>[25]</sup>. Electronic structures of the pristine  $C_{60}$  and alkali-doped  $C_{60}$  are summarized as follows<sup>[26]</sup>. (i) In the pristine  $C_{60}$  which is of the face center cubic (fcc) structure, the highest occupied band (valence band) named  $h$ , is fivefold degenerate, and the lowest unoccupied band (conduction band) named  $t_{1u}$  is triply degenerate at the Brillouin zone center. (ii) The next lowest conduction band named  $t_{1g}$ , also triply degenerate, is located about 1 eV above the  $t_{1u}$  band. (iii) In alkali-doped  $C_{60}$  (fulleride)  $A_xC_{60}$ , electrons of alkali atoms are transferred to  $\pi$  orbitals of  $C_{60}$  balls, since the ionization energy of an alkali atom (K, Rb, Cs) is much smaller than that of a  $C_{60}$  ball. (iv) In the superconducting fcc  $A_3C_{60}$ , the alkali atoms occupy every tetrahedral and octahedral interstitial sites, and the  $t_{1u}$  band is half filled with the transferred electrons. Hence this material is an ionic metal. (v) The  $A_6C_{60}$  is experimentally an insulator. This is simply explained by the fact that 6 electrons are enough to fill the  $t_{1u}$  conduction band. (vi) It is also found<sup>[27]</sup> that there is a unique linear relation between the observed  $T_c$  and the calculated Density of States near Fermi level

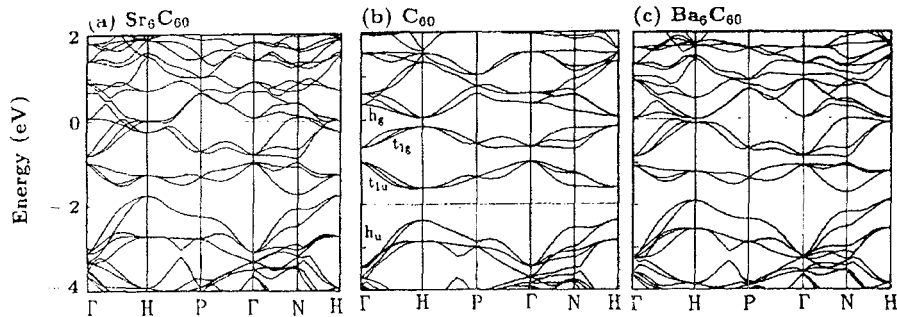


Figure 7: Energy-band structures of (a)  $\text{Sr}_6\text{C}_{60}$ , (b) hypothetical undoped bcc  $\text{C}_{60}$ , and (c)  $\text{Ba}_6\text{C}_{60}$ . Energy is measured from the Fermi level denoted by the horizontal lines.

in pressurized  $\text{K}_3\text{C}_{60}$  and  $\text{Rb}_3\text{C}_{60}$ .

It was recently found that alkaline-earth doping also produces superconductivity:  $\text{Ca}_5\text{C}_{60}$  ( $T_c = 8\text{K}$ )<sup>[28]</sup>,  $\text{Ba}_6\text{C}_{60}$  ( $T_c = 7\text{K}$ )<sup>[29]</sup>, and  $\text{Sr}_6\text{C}_{60}$  ( $T_c = 4\text{K}$ )<sup>[30]</sup>. The latter two are particularly interesting since their crystal structure (body centered cubic (bcc)) and the composition are identical to alkali-doped  $\text{A}_6\text{C}_{60}$  which is an insulator. Naive thinking leads to a conclusion that  $\text{Ba}_6\text{C}_{60}$  and  $\text{Sr}_6\text{C}_{60}$  are also insulating, since full charge transfer results in the complete occupancy of the  $t_{1u}$  and the next lowest  $t_{1g}$  conduction bands. We have found that this is not the case, however. The reason is hybridization between  $\pi$  orbital of the ball and the alkaline-earth orbitals, in particular,  $d$  orbitals<sup>[31]</sup>.

Fig. 7 shows calculated energy bands of  $\text{Sr}_6\text{C}_{60}$  and  $\text{Ba}_6\text{C}_{60}$ . In  $\text{Sr}_6\text{C}_{60}$ , the  $t_{1u}$  conduction bands are completely occupied. The next lowest band  $t_{1g}$  is partially occupied, since it hybridizes with  $4d$  state of Sr and the upper  $\pi$  band. As a result,  $\text{Sr}_6\text{C}_{60}$  is the first example of semimetallic fullerenes. A possible reason for this strong hybridization could be a reduction of the inter-ball distance: In  $\text{Sr}_6\text{C}_{60}$ , the distance between  $\text{C}_{60}$  clusters is 9.53 Å, 5% shorter than the value in pristine  $\text{C}_{60}$ . But this is not the answer. Fig. 7(b) is the energy bands of hypothetical undoped bcc  $\text{C}_{60}$  which has the identical structure with  $\text{Sr}_6\text{C}_{60}$ . The energy bands of this hypothetical  $\text{C}_{60}$  are significantly different from those of  $\text{Sr}_6\text{C}_{60}$ . Rather, the bands in Fig. 7(b) is almost identical to the bands of  $\text{K}_6\text{C}_{60}$ <sup>[32]</sup>.

The situation is the following. For a neutral Sr atom, the  $5s$  level is occupied by 2 electrons. The ion-

ization energy is smaller than that of  $\text{C}_{60}$  cluster so that the electron is transferred to  $\pi$  orbitals in Sr-doped  $\text{C}_{60}$ . When the Sr is ionized, however, the  $4d$  level is lowered and close to the  $5s$  level. Further, in  $\text{Sr}_6\text{C}_{60}$  the Sr atom has a high coordination number; there exist 5 or 6 neighbor carbon atoms. This coordination number favors the  $d$  state with which the  $\pi$  orbitals are hybridized. Hence the electron is transferred from the  $5s$  state to the  $\pi$  state, and partially transferred back to the  $4d$  state. This combination of charge transfer and the hybridization renders the material semimetallic. At the same time, the interball distance is reduced; i.e., the hybridization works as a glue for the soccer balls.

In  $\text{Ba}_6\text{C}_{60}$ , the situation is essentially same with  $\text{Sr}_6\text{C}_{60}$ . Fig. 7(c) is the energy bands of  $\text{Ba}_6\text{C}_{60}$ . It is again a semimetal. But in this case, the  $5d$  level of Ba is slightly higher than the  $4d$  level of Sr. Then the mixing between the  $t_{1g}$  and the  $5d$  becomes less prominent so that the density of states near the Fermi level is smaller than that in  $\text{Sr}_6\text{C}_{60}$ . A new feature, however, has come up in this case. That is the inter-ball or the intra-ball state. This state has the amplitude both within and between the soccer balls, and not on atomic sites. The intra- and inter-ball state is an analogy of the interlayer state in graphite intercalation compounds, and generally exists in anisotropic materials or the materials with large vacant spaces. In the case of  $\text{Ba}_6\text{C}_{60}$ , the state is situated at about 1 eV above the Fermi level, and pushes  $5d$  and the upper  $\pi$  states toward the Fermi level. This is the reason why  $\text{Ba}_6\text{C}_{60}$  also becomes a semimetal.

## VI. In short

I have presented our LDA calculations for a defect in Si, an initial stage of heteroepitaxy, and an alkaline-earth doped  $C_{60}$ . Of course, there remain several issues unclarified. But the LDA calculations provide us fair description of the phenomena in a variety of materials.

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